

FIG. 1

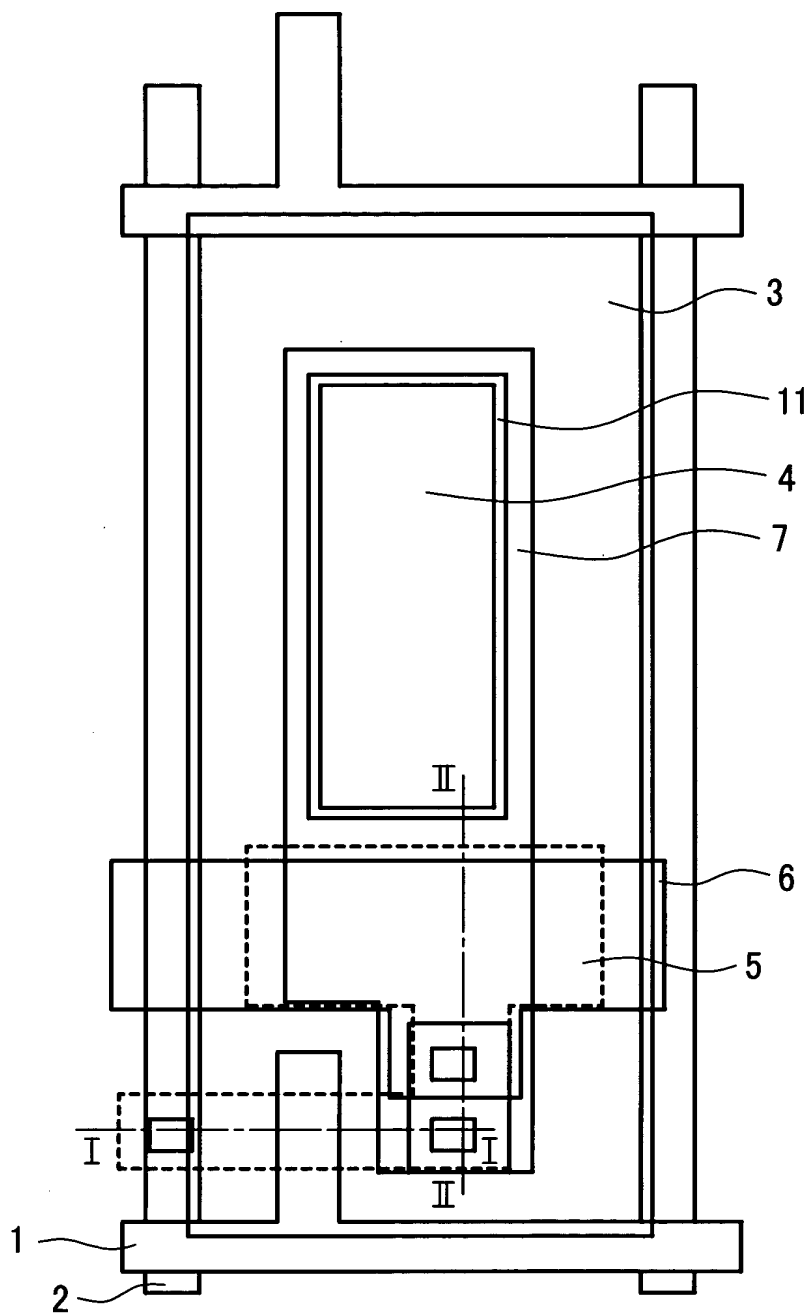


FIG. 2

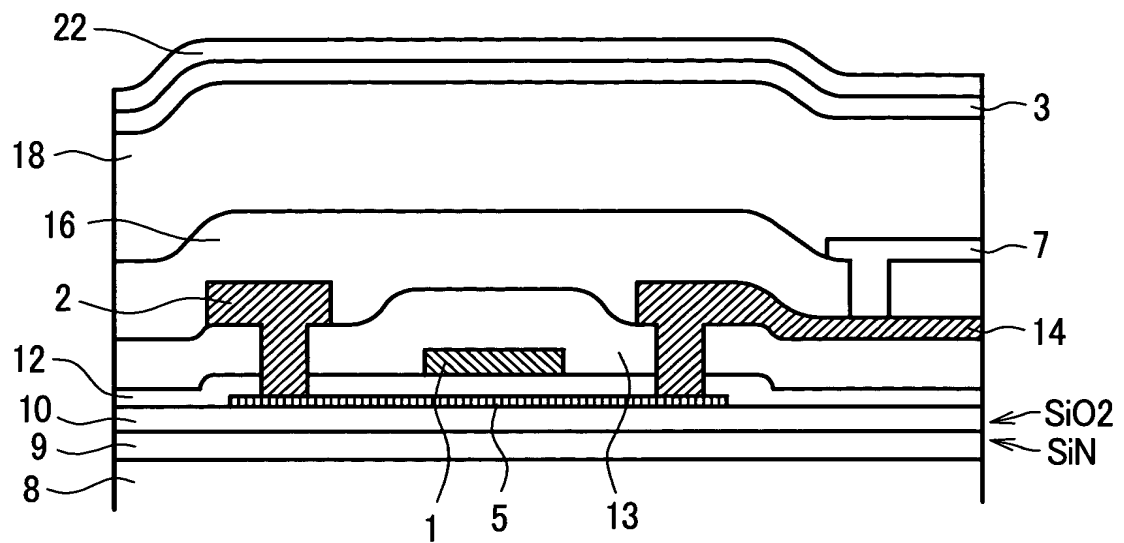


FIG. 3

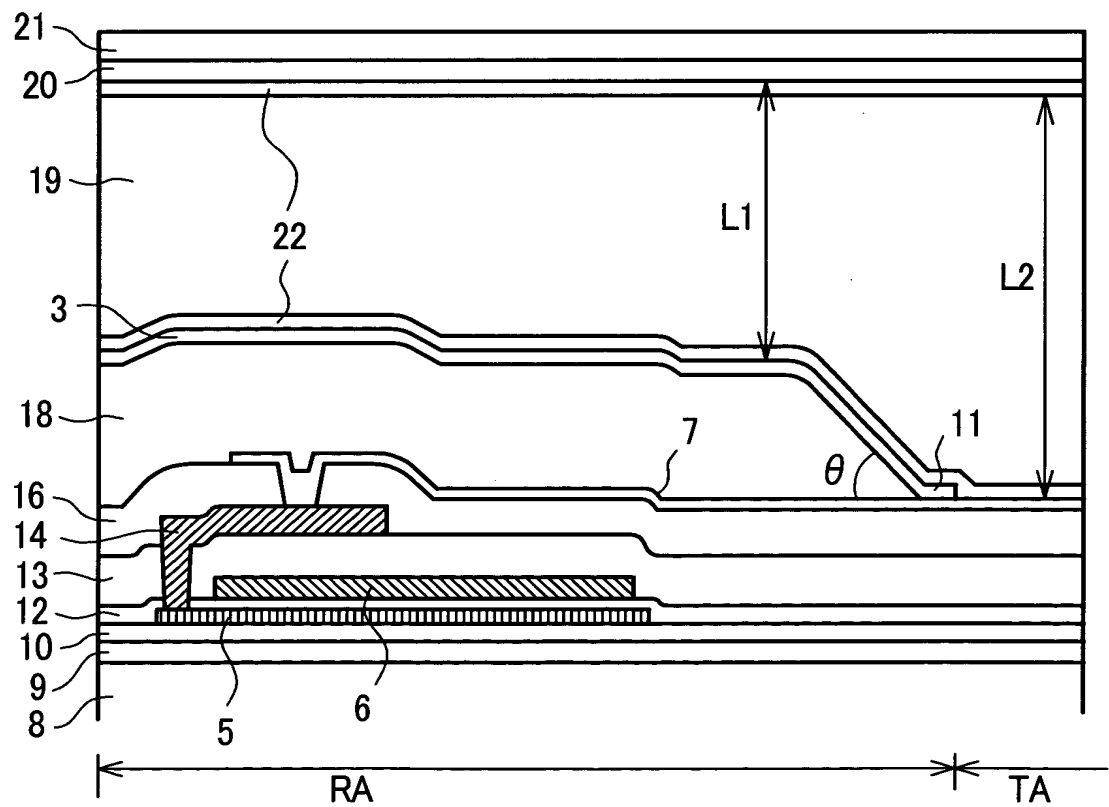


FIG. 4

	Material	d (nm)	n (Wave length : 555nm)
Orientation film/LC	Orientation film/LC		1.5
Transparent electrode	ITO	77	2.0
2nd. insulating film	SiO ₂	200	2.0
1st. insulating film	SiO ₂	540	1.5
Gate insulating layer	SiO ₂	100	1.5
2nd. lower layer	SiO ₂	100	1.5
1st. lower layer	SiN	50~180	2.0
Substrate	Glass		

FIG. 5

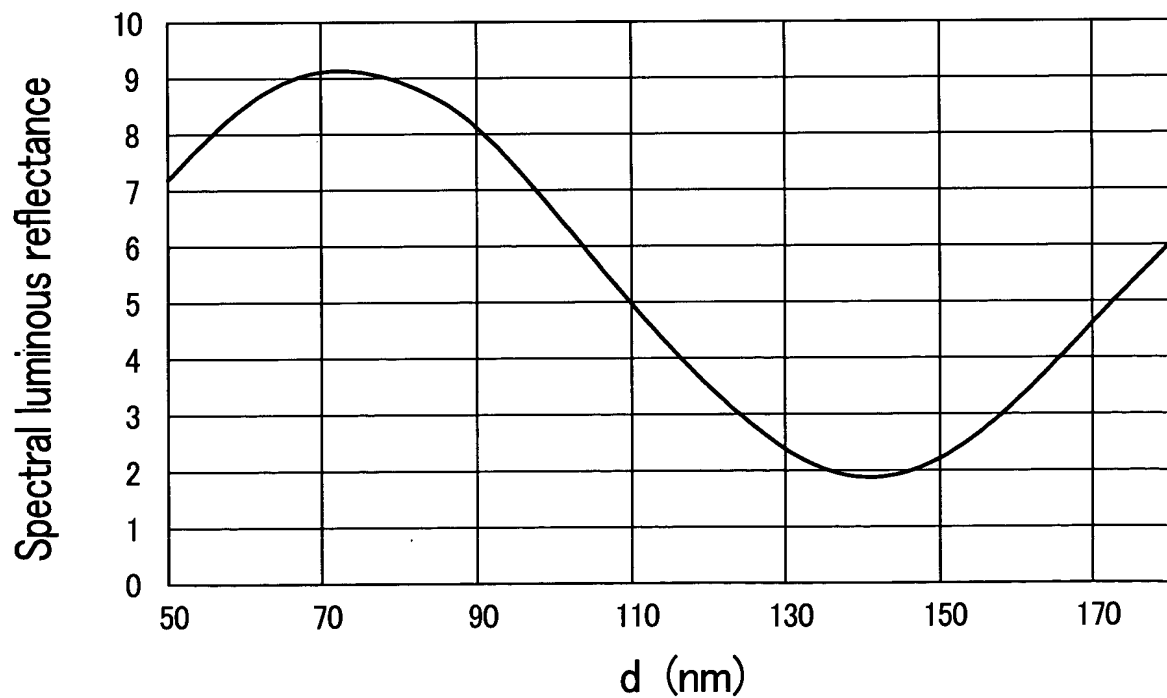


FIG. 6

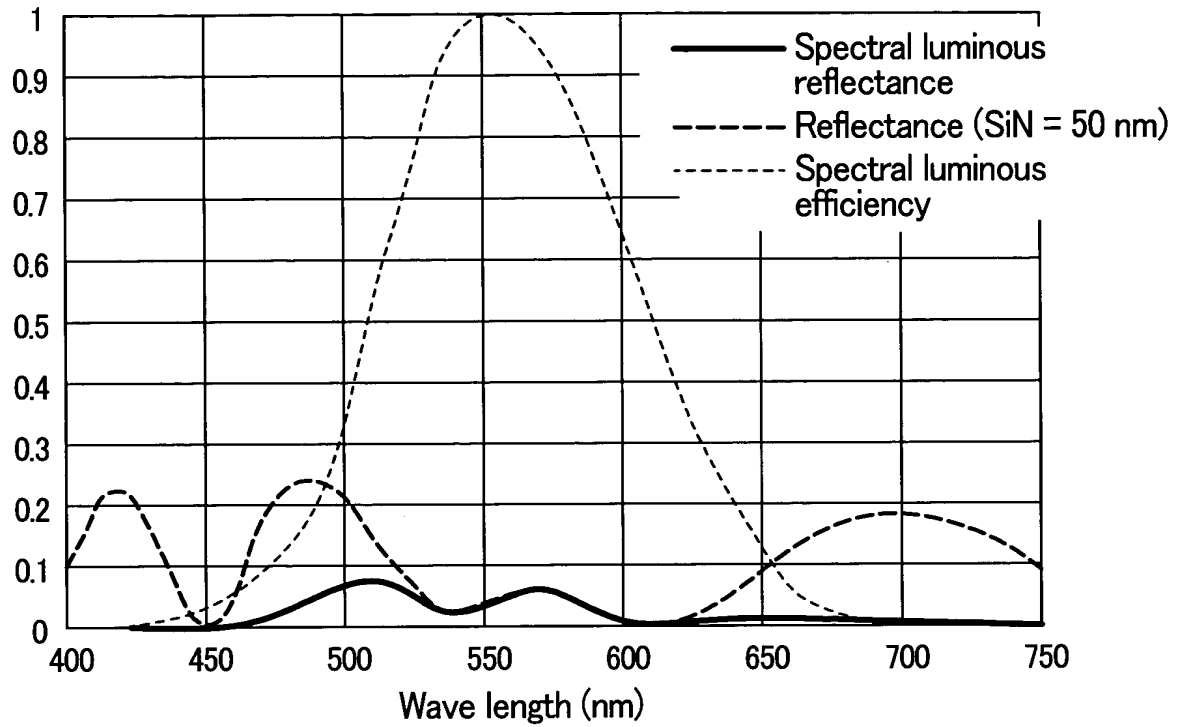


FIG. 7

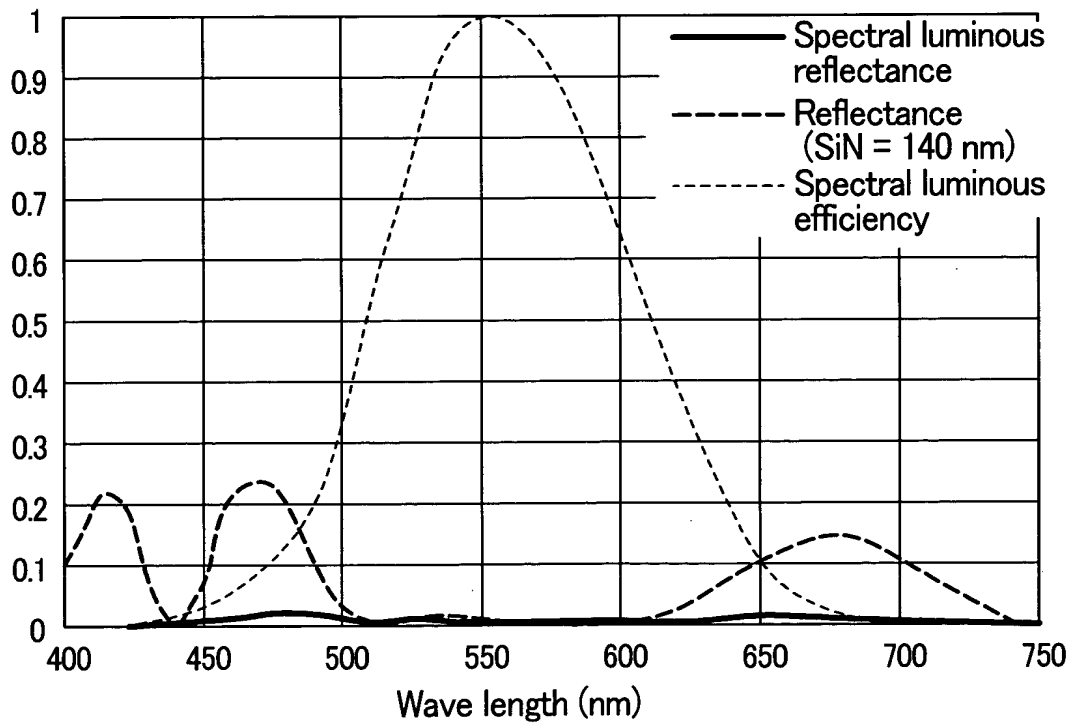


FIG. 8

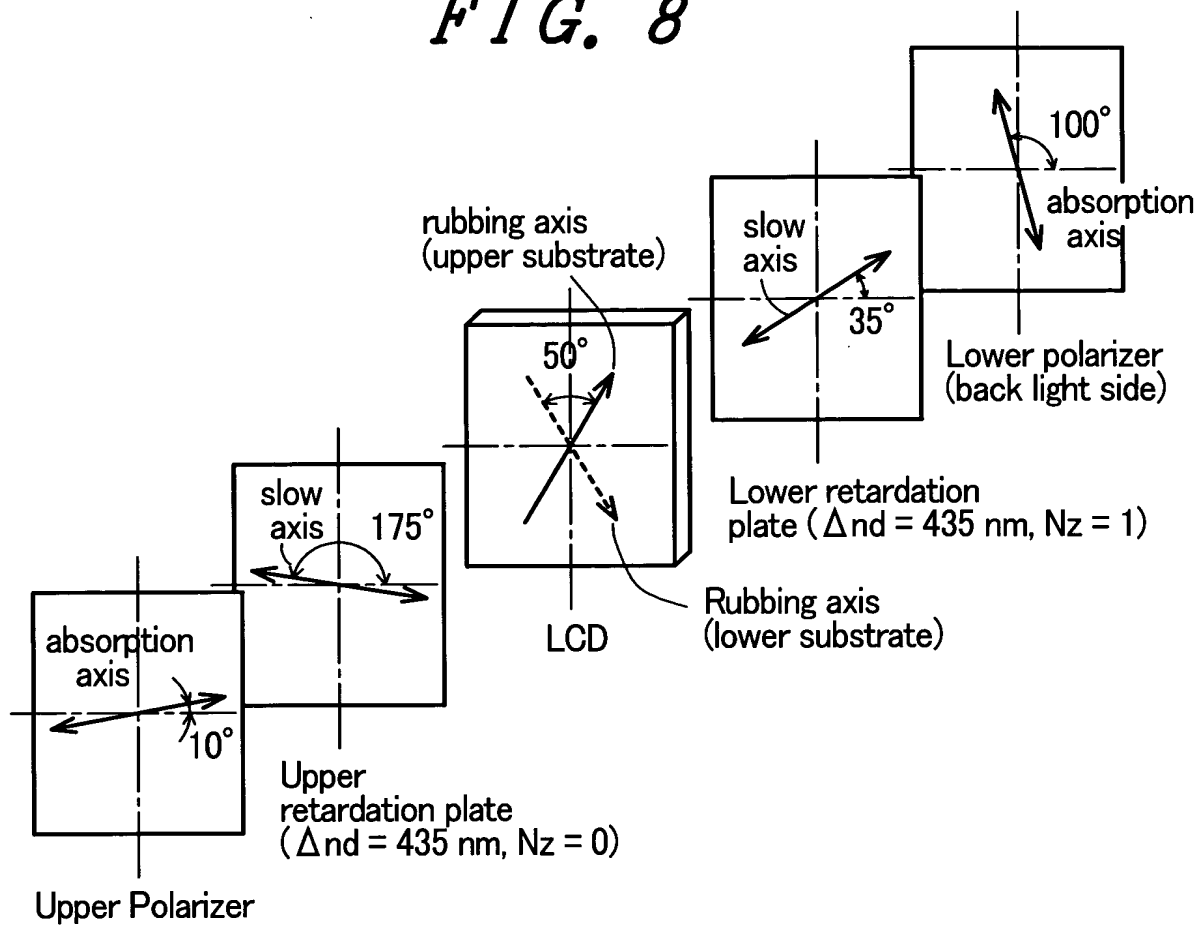


FIG. 9

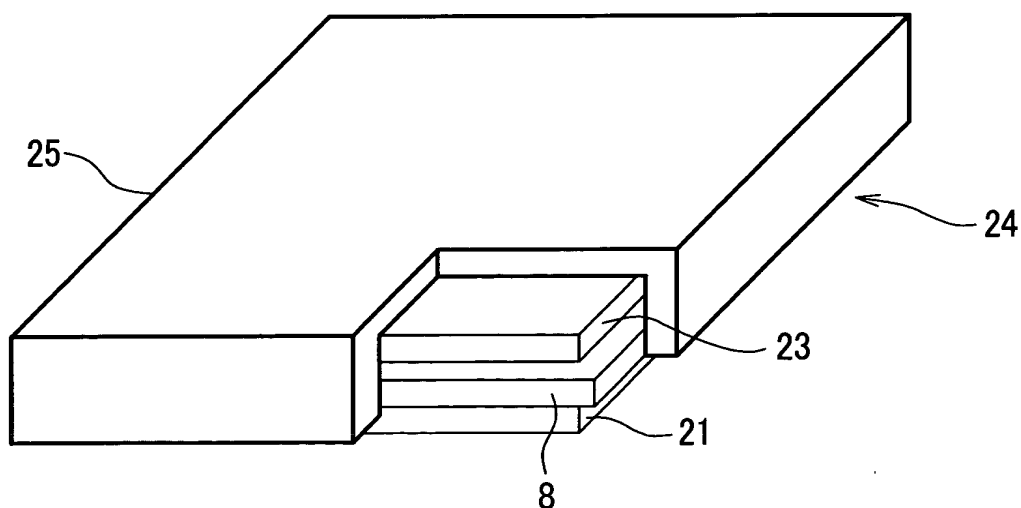
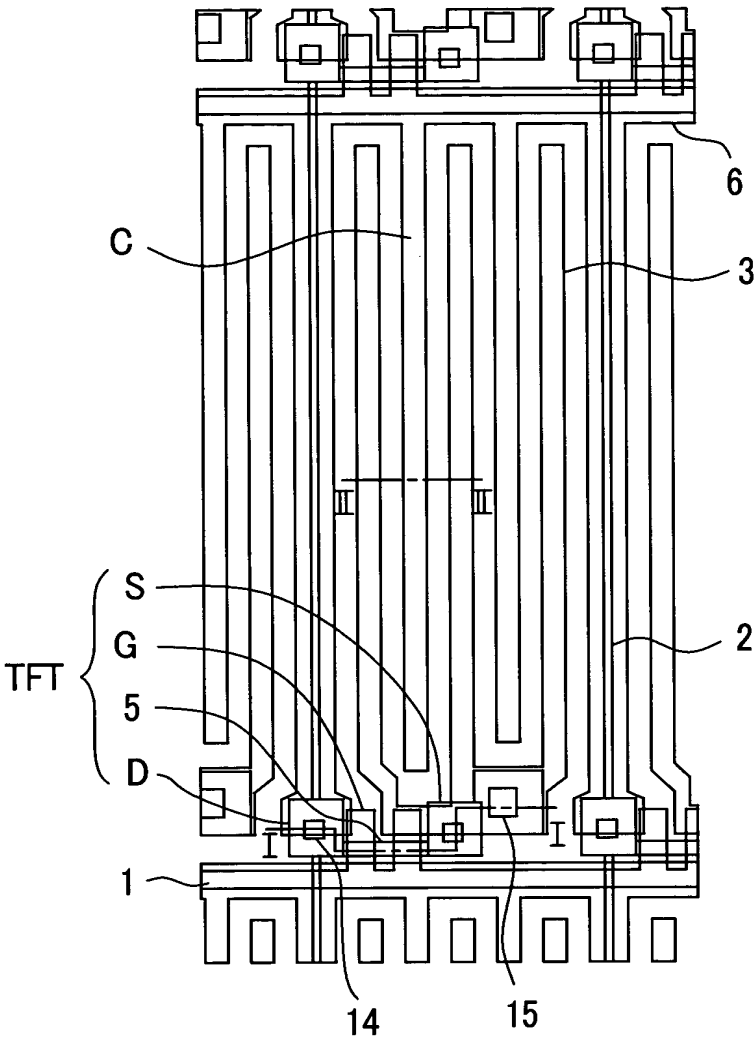


FIG. 10



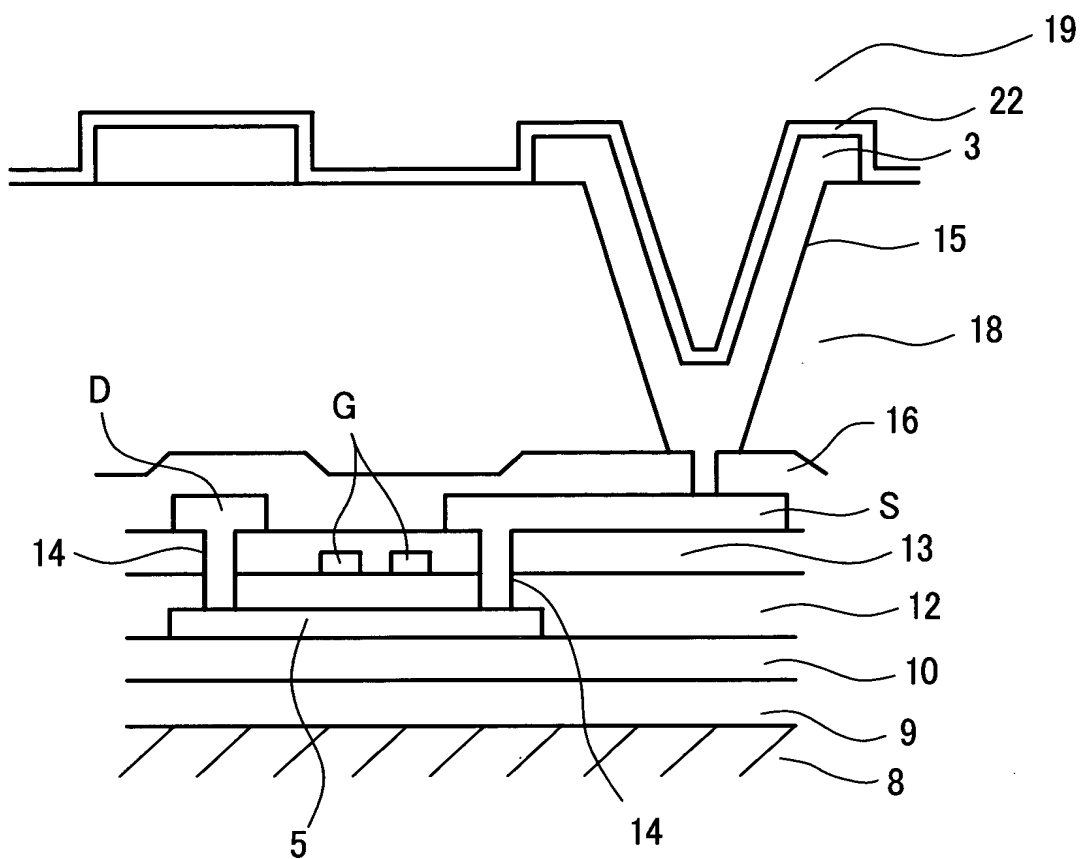
[illegible]

FIG. 12

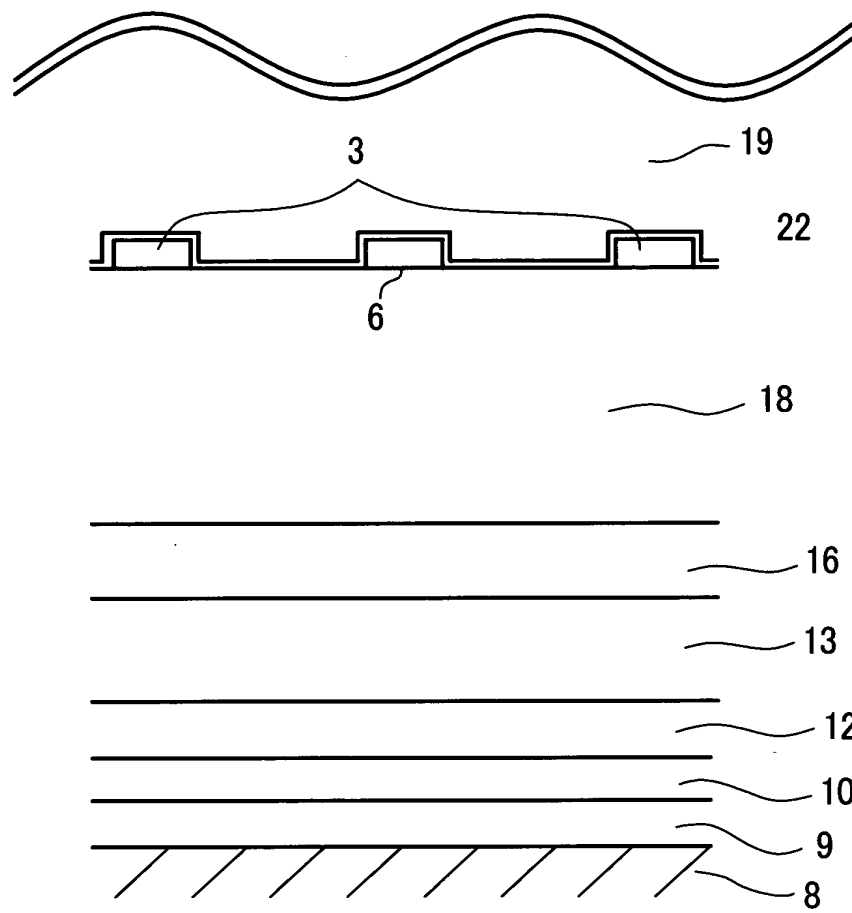


FIG. 13

	Material	d (nm)	n (Wave length : 555nm)
Orientation film/LC	Orientation film/LC	5200	1.5
Transparent electrode	ITO	140	2.0
Passivation film	Organic film	1730	1.6
2nd. insulating film	SiO ₂	300	1.85
1st. insulating film	SiO ₂	540	1.5
Gate insulating layer	SiO ₂	100	1.5
2nd. lower layer	SiO ₂	100	1.5
1st. lower layer	SiN	150	1.85
Substrate	Glass	—	1.5

FIG. 14

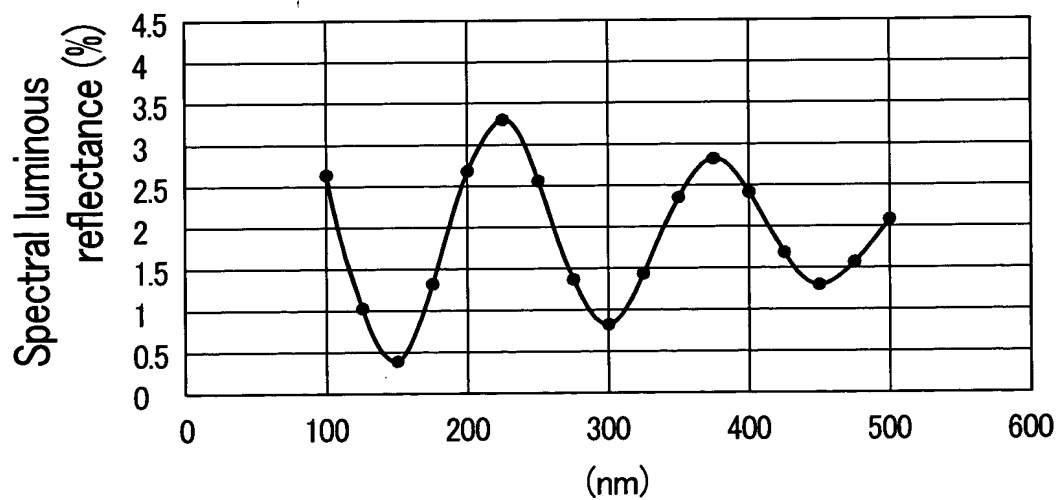


FIG. 15

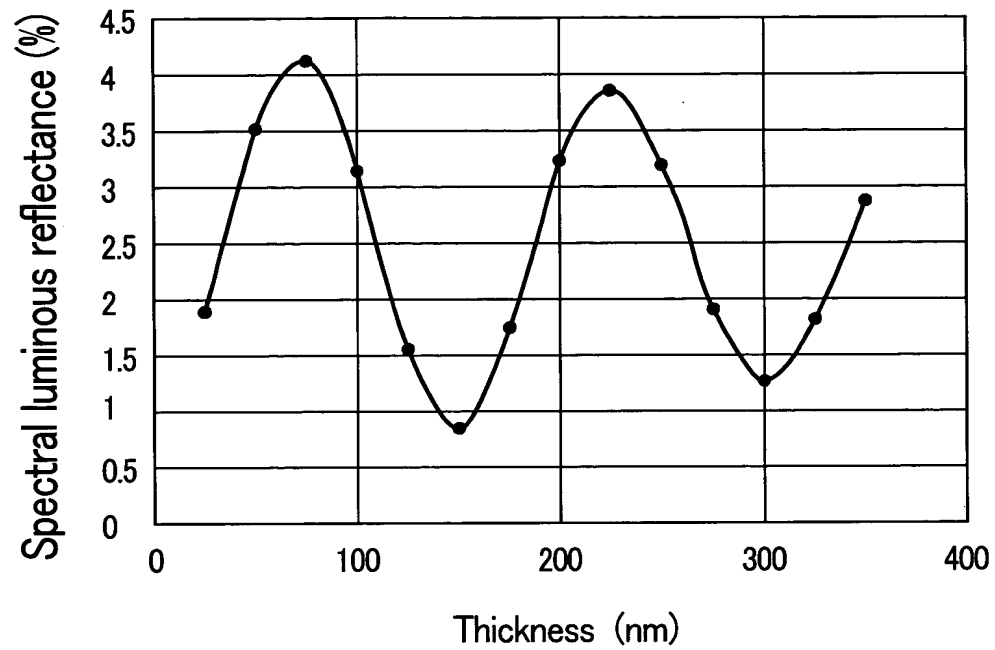


FIG. 16

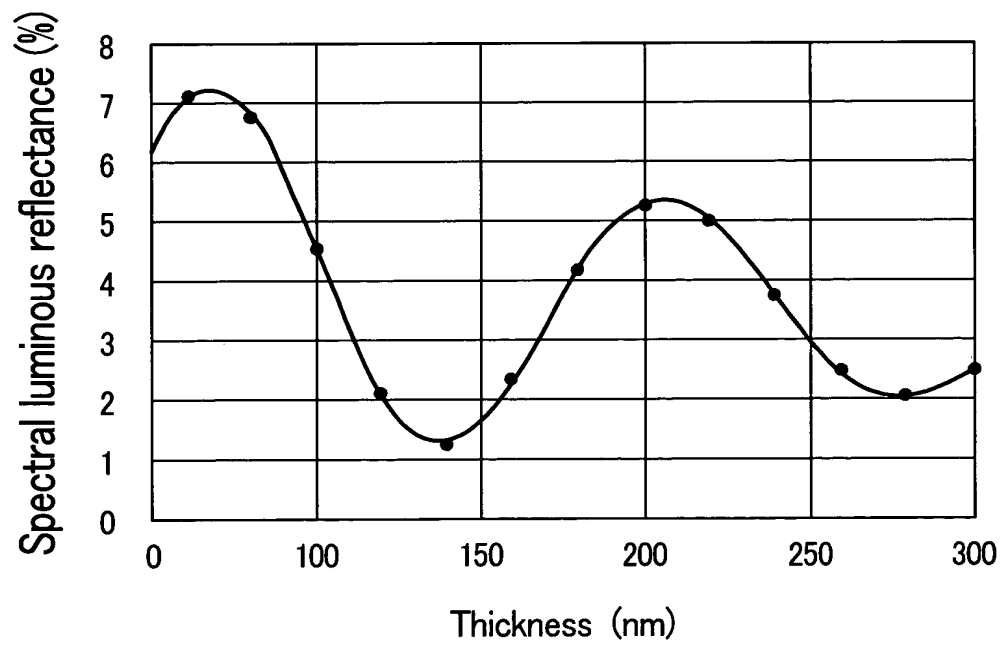


FIG. 17

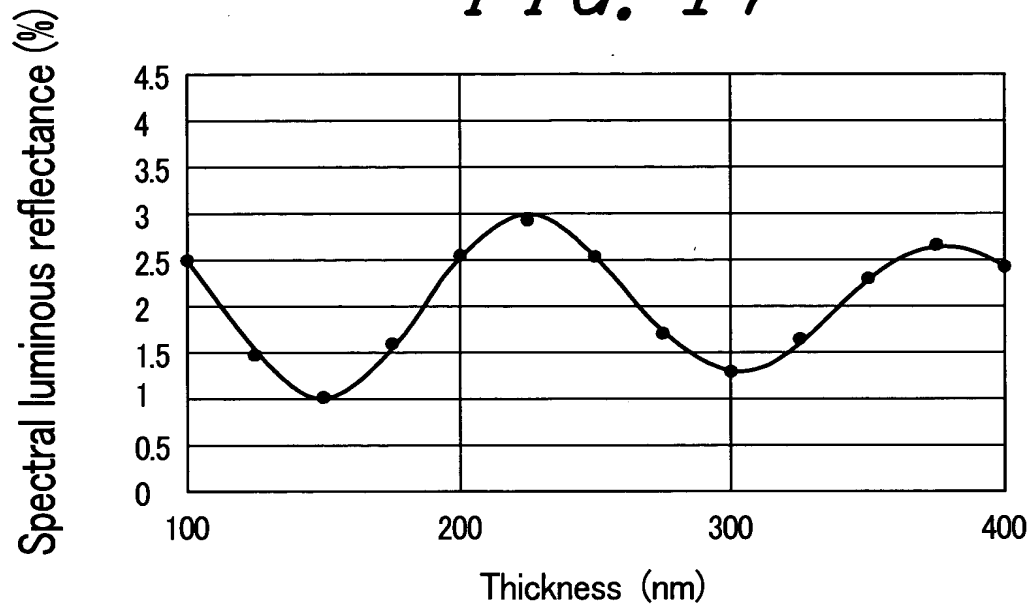


FIG. 18

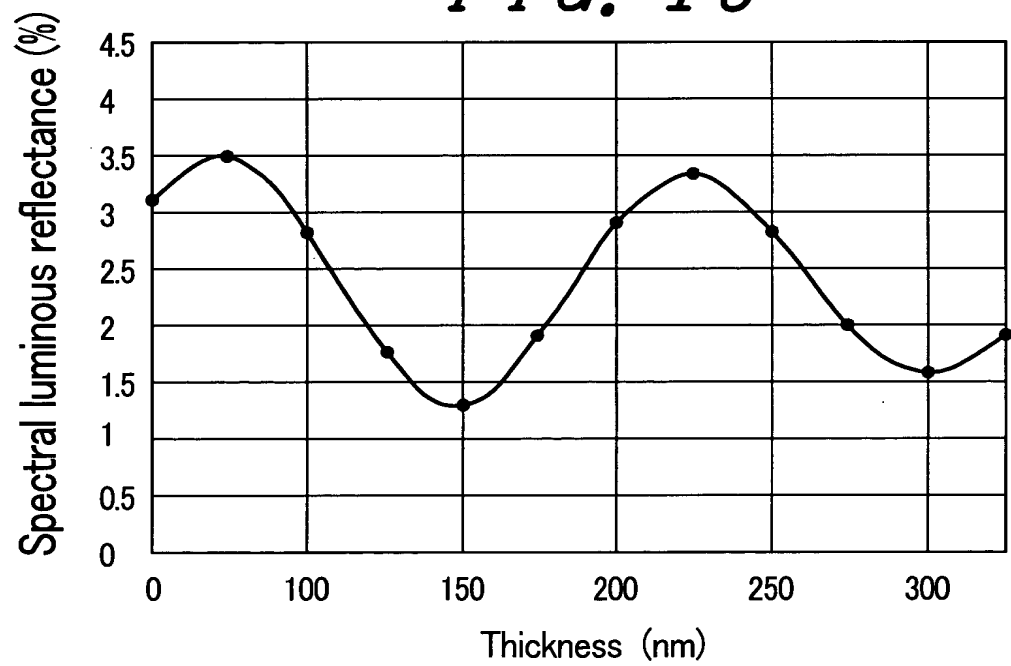


FIG. 19

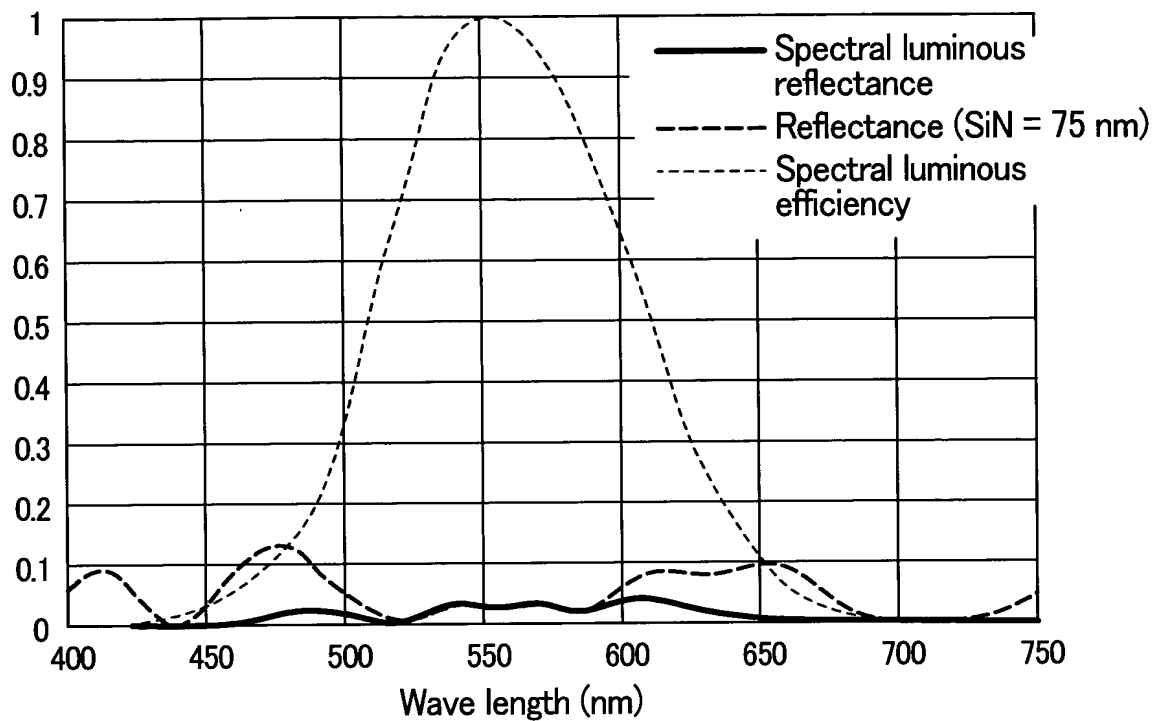


FIG. 20

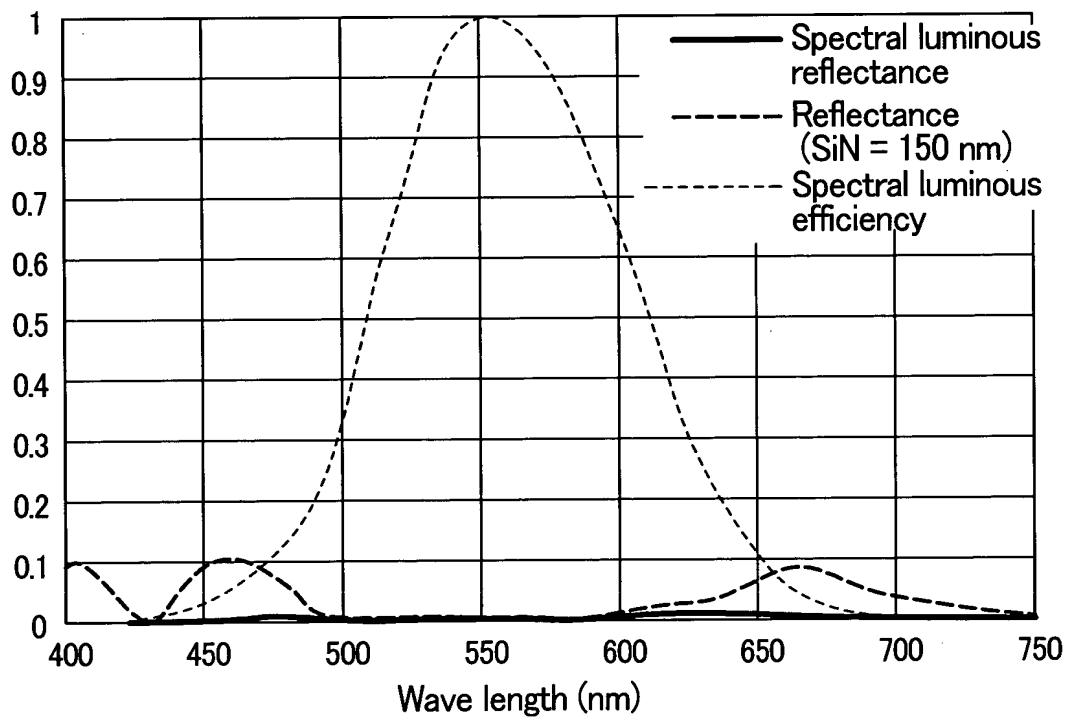


FIG. 21

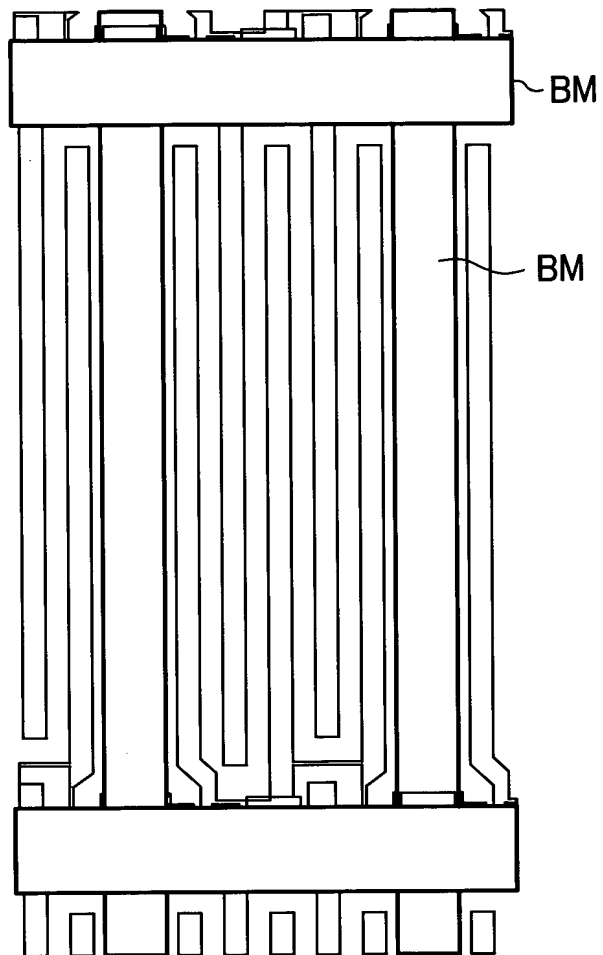


FIG. 22

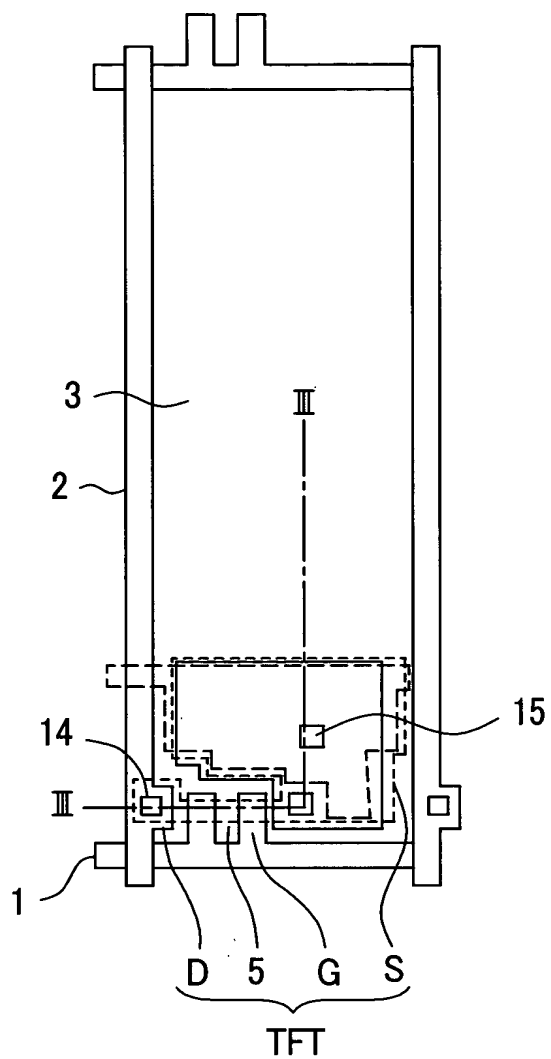


FIG. 23

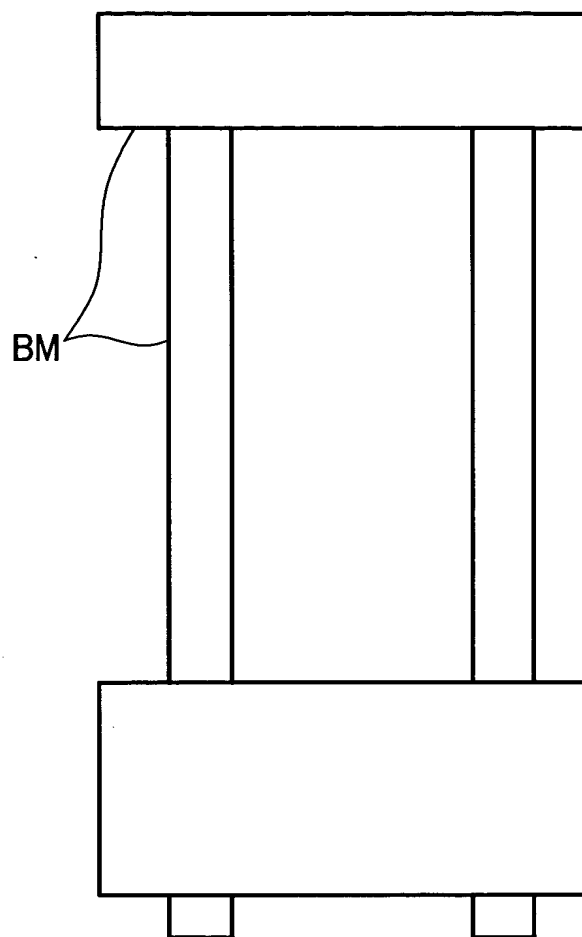


FIG. 24

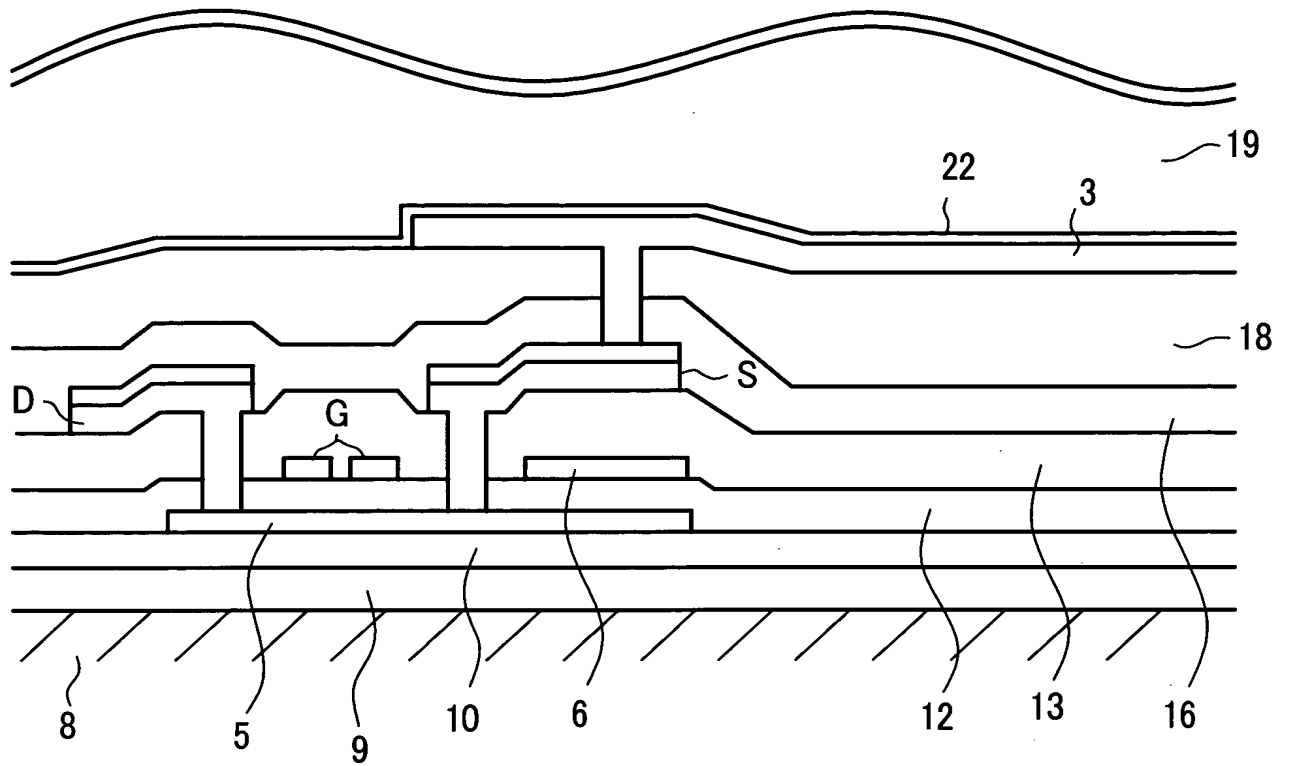


FIG. 25

